



Novel Plasma Science, Technology, and Medicine

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Deadline for manuscript
submissions:

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Message from the Guest Editor

Dear Colleagues,

Plasma is an ionised gas, used in the production of microelectronics for decades. In the last decade or so, plasma has emerged as an appealing alternative to existing technologies, because of its potential in intermittent operation, decentralised deployment, and compatibility with renewable electricity. Recent developments demonstrate the tremendous advances in plasma applications for N₂ fixation, CO₂ and N₂O conversion, dry reforming of CH₄, etc. Besides, plasma is also an invaluable tool in medicine, actively researched as an anti-microbial, anti-cancer, wound healing and dental agent.

We welcome manuscripts on all aspects of plasma research: from developing plasma power supplies and reactors to process optimization, from optical analyses to medicinal plasma studies, with both applied and fundamental science discoveries

Keywords

- atmospheric pressure plasma
- plasma medicine
- sustainability
- plasma nitrogen fixation
- plasma DRM
- plasma for microelectronics





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Message from the Editor-in-Chief

As the world of science becomes ever more specialized, researchers may lose themselves in the deep forest of the ever increasing number of subfields being created. This open access journal *Applied Sciences* has been started to link these subfields, so researchers can cut through the forest and see the surrounding, or quite distant fields and subfields to help develop his/her own research even further with the aid of this multi-dimensional network.

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